



Nanoplasmonics: Emerging Field of Nanophotonics

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Although plasmonic phenomena were identified more than half century ago, with the rapid advancements of photonics, computation, and nanofabrication techniques, the area of plasmonics has achieved remarkable developments in both fundamental principles and various practical applications, including subwavelength imaging, lithography, microscopy, spectroscopy, optical interconnects, optical trapping and sensing, etc. Recently, the main effort has been to combine it with new physics, materials, and techniques such as deep ultraviolet/extreme ultraviolet sources, two-dimensional materials, quantum plasmonics, and many more to search for exciting phenomena and applications.

This Special Issue invites manuscripts that introduce recent advances in “Nanoplasmonics: Emerging Field of Nanophotonics”. All theoretical, numerical, and experimental papers are accepted. Topics include, but are not limited to, the following:

- Plasmonic-based super resolution imaging;
- Plasmonic-based lithography and fabrication;
- Plasmonic metasurfaces and metamaterials;
- Deep ultraviolet/extreme ultraviolet plasmonic;
- Plasmonics in two-dimensional materials;
- Nonlinear plasmonics;
- Quantum plasmonics;
- Plasmonic optical trapping;
- Plasmonic optical waveguides;
- Plasmonic spectroscopy and sensing;
- Plasmonics with microfluidics.

